

IN THE ABSTRACT:

Please amend the abstract by inserting the abstract presented in the substitute specification being filed concurrently herewith.

ABSTRACT OF THE DISCLOSURE

A projection exposure apparatus includes a continuous emission excimer laser for providing laser light having a predetermined wavelength, an illumination optical system for illuminating a pattern of a reticle with laser light having the predetermined wavelength, a projection optical system for projecting the illuminated pattern of the reticle onto a substrate, wherein the projection optical system is provided by a lens system made of a substantially single glass material, a laser for injecting light having the predetermined wavelength into a resonator of the continuous emission excimer laser, a wavemeter for measuring the wavelength of the laser light from the continuous emission excimer laser, and a changing device for changing a resonator length of the continuous emission excimer laser on the basis of a signal from the wavemeter so that the wavelength of the laser light from the continuous emission excimer laser becomes equal to the predetermined wavelength.